

10649645_CLS
Most Frequently Occurring Classifications of Patents Returned
From A Search of 10649645 on July 28, 2004

Original Classifications

7 250/492.2
7 250/492.22
6 430/296
4 250/491.1
3 355/53
2 356/500
2 430/30
2 430/5

Cross-Reference Classifications

7 250/398
7 250/492.2
6 250/492.22
6 430/942
5 430/296
3 250/396R
3 250/492.23
3 250/492.3
3 355/67
3 430/5
2 250/397
2 250/491.1
2 250/492.1
2 430/426

Combined Classifications

14 250/492.2
13 250/492.22
11 430/296
7 250/398
6 250/491.1
6 430/942
5 430/5
4 250/396R
4 355/53
3 250/397
3 250/492.23
3 250/492.3
3 355/67
2 250/310
2 250/492.1
2 356/500
2 430/30

10649645_CLS

2 430/426

10649645_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

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14 250/492.2 (7 OR, 7 XR)
 Class 250 : RADIANT ENERGY
 250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
 250/492.2 .Irradiation of semiconductor devices

13 250/492.22 (7 OR, 6 XR)
 Class 250 : RADIANT ENERGY
 250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
 250/492.2 .Irradiation of semiconductor devices
 250/492.22 ..Pattern control

11 430/296 (6 OR, 5 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
 RADIATION SENSITIVE MATERIAL, OR PRODUCING
 NONPLANAR OR
 PRINTING SURFACE - PROCESS, COMPOSITION, O
 R PRODUCT
 430/296 .Electron beam imaging

7 250/398 (0 OR, 7 XR)
 Class 250 : RADIANT ENERGY
 250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
 FOCUSSING
 250/398 .With target means

6 250/491.1 (4 OR, 2 XR)
 Class 250 : RADIANT ENERGY
 250/491.1 MEANS TO ALIGN OR POSITION AN OBJECT RELATIVE
 TO A SOURCE OR DETECTOR

6 430/942 (0 OR, 6 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/942 ELECTRON BEAM

5 430/5 (2 OR, 3 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/4 RADIATION MODIFYING PRODUCT OR PROCESS OF
 MAKING
 430/5 .Radiation mask

10649645_CLSTITLES

- 4 250/396R (1 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING
- 4 355/53 (3 OR, 1 XR)
Class 355 : PHOTOCOPYING
355/18 PROJECTION PRINTING AND COPYING CAMERAS
355/53 .Step and repeat
- 3 250/397 (1 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING
250/397 .With detector
- 3 250/492.23 (0 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
250/492.23 ..Variable beam
- 3 250/492.3 (0 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.3 .Ion or electron beam irradiation
- 3 355/67 (0 OR, 3 XR)
Class 355 : PHOTOCOPYING
355/18 PROJECTION PRINTING AND COPYING CAMERAS
355/67 .Illumination systems or details
- 2 250/310 (1 OR, 1 XR)
Class 250 : RADIANT ENERGY
250/306 INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED
PARTICLES
250/310 .Electron probe type
- 2 250/492.1 (0 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
- 2 356/500 (2 OR, 0 XR)
Class 356 : OPTICS: MEASURING AND TESTING
356/450 BY LIGHT INTERFERENCE (E.G., INTERFEROMETER)
356/496 .For dimensional measurement
356/498 ..Displacement or distance

10649645 CLSTITLES
356/500 ...X-Y and/or Z table

2 430/30 (2 OR, 0 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/30 INCLUDING CONTROL FEATURE RESPONSIVE TO A TEST
OR MEASUREMENT

2 430/426 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/401 POST IMAGING PROCESSING
430/423 .Treating with processing composition after
imaging prior to developing
430/426 ..Prehardening